

REMARKS

Claims 1-11 are pending in this application. Claims 5-7 and 9-11 have been withdrawn from consideration.

Claims 1-2 and 8 were rejected under 35 U.S.C. §102(e) as being anticipated by U.S. Patent No. 6,897,007 (hereinafter "Okamoto"). This rejection is respectfully traversed.

With respect to claim 8, the Office Action acknowledges that Okamoto fails to disclose all the features of this claim. (See pgs. 5-6).

Okamoto fails to teach or suggest the second exposure step of performing exposure for the developed photosensitive resin layer at a substrate temperature of 100 to 250°C with an illuminance of 80 mW/cm² or more and an irradiation energy of greater than 10 J/cm² to less than or equal to 30 J/cm², as recited by claim 1.

Okamoto discloses a method for forming an image including exposing a photosensitive lithographic printing plate having a photosensitive layer. Okamoto discloses that image formation is carried out by subjecting the photosensitive layer of the photosensitive lithographic printing plate to scanning exposure with a laser light having a wavelength range of from 650 to 1300 nm, developing the image, and then subjecting the whole surface to post-exposure.

Okamoto discloses that, after the development treatment, the image formation method carries out the whole image exposure with an exposure energy of at most 70 times greater (most preferably at most 15 times greater) than that of the scanning exposure with the laser light. (See col. 15, lines 60-64). Okamoto explicitly discloses that carrying out the whole image exposure with an exposure energy greater than 70 times greater than that of the scanning exposure with the laser light results in an image strength lacking a satisfactory printing resistance. (See col. 16, lines 5-9).

In order to maintain this relationship between the exposure energy of the whole image exposure and the exposure energy of the scanning exposure, Okamoto discloses carrying out whole image exposure with an exposure energy in a range of 10 mJ/cm^2 to 10 J/cm^2 . Thus, Okamoto fails to teach or suggest the second exposure step of performing exposure for the developed photosensitive resin layer at a substrate temperature of 100 to 250°C with an illuminance of 80 mW/cm^2 or more and the radiation energy of greater than 10 J/cm^2 to less than or equal to 30 J/cm^2 , as recited by claim 1.

Although Okamoto discloses a more preferable range of 50 MJ/cm^2 to 10 J/cm^2 , this is clearly a typographical error. Clearly, 50 mJ/cm^2 was intended because all other ranges disclosed by Okamoto are presented as increasing from a lower limit to an upper limit. Moreover, 50 MJ/cm^2 cannot be correct because it would result in the preferably disclosed range not falling within the previously disclosed broader range (i.e. 10 mJ/cm^2 to 10 J/cm^2).

Therefore, claim 1 is patentable over Okamoto. Accordingly, withdrawal of the rejection is respectfully requested.

Claim 3 was rejected under 35 U.S.C. §103(a) as being unpatentable over Okamoto in view of U.S. Patent No. 4,373,018 (hereinafter "Reichmanis") and claims 4 and 8 were rejected under 35 U.S.C. §103(a) as being unpatentable over Okamoto in view of U.S. Patent No. 6,335,149 (hereinafter "Xu"). These rejections are respectfully traversed.

Reichmanis and Xu fail to provide at least that which Okamoto lacks. Accordingly, withdrawal of the rejections is respectfully requested.

Withdrawn claims 5-7 and 9-11 depend from claim 1. Thus, upon allowance of claim 1, rejoinder and allowance of claims 5-7 and 9-11 are respectfully requested. (See MPEP §821.04)

In view of the foregoing, Applicants respectfully submit that this application is in condition for allowance. Favorable reconsideration and prompt allowance are earnestly solicited.

Should the Examiner believe that anything further is desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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